

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	48439	(PECvD or HDPCvD or ((Cvd or (chemical adj vapor\$6 adj deposit\$6)) near5 (plasma or PE or HDP))) and (dielectric or insulat\$6 or SiCO or SiOC or ((Silicon or Si) near5 (oxide or dioxide or oxycarbide or hydrocarbon or carbon or methyl)) or (Si?sub\$3 near3 C?sub\$3 near3 O?sub\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:33
L2	24585	1 and (CMP or polish\$6 or hardmask or hardness or etchstop\$6 or polishstop\$6 or stop\$6 or GPa)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:31
L3	19468	2 and (@ad<="20020909" or @rlad<="20020909")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:30
L4	123204	(dielectric or insulat\$6 or SiCO or SiOC or ((Silicon or Si) near5 (oxide or dioxide or oxycarbide or hydrocarbon or carbon or methyl)) or (Si?sub\$3 near3 C?sub\$3 near3 O?sub\$3)) same (CMP or polish\$6 or hardmask or hardness or etchstop\$6 or polishstop\$6 or stop\$6 or GPa)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:32
L5	12571	3 and 4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:32
L6	31787	(PECvD or HDPCvD or ((Cvd or (chemical adj vapor\$6 adj deposit\$6)) near5 (plasma or PE or HDP))) same (dielectric or insulat\$6 or SiCO or SiOC or ((Silicon or Si) near5 (oxide or dioxide or oxycarbide or hydrocarbon or carbon or methyl)) or (Si?sub\$3 near3 C?sub\$3 near3 O?sub\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:36
L7	9907	5 and 6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:34

L8	1938	7 and (situ or insitu or ("same" adj (chamber or reactor or processor or apparatus)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:35
L9	1138	(PECvD or HDPCvD or ((Cvd or (chemical adj vapor\$6 adj deposit\$6)) near5 (plasma or PE or HDP))) same (dielectric or insulat\$6 or SiCO or SiOC or ((Silicon or Si) near5 (oxide or dioxide or oxycarbide or hydrocarbon or carbon or methyl)) or (Si?sub\$3 near3 C?sub\$3 near3 O?sub\$3)) same (situ or insitu or ("same" adj (chamber or reactor or processor or apparatus)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:37
L10	517	8 and 9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/02 10:37